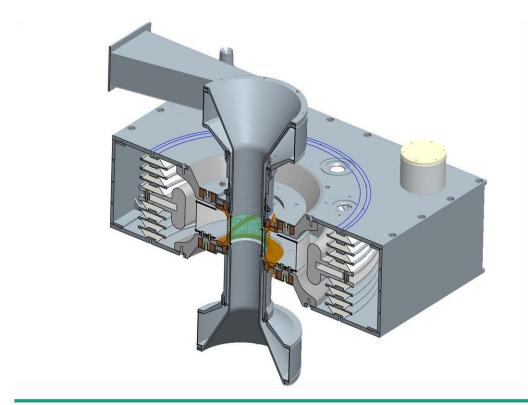
### **A NOVEL ELECTRON BEAM SOURCE** - for simplified irradiation of 3D-shaped surfaces -



Workshop – Industrial and environmental application of electron beams Warschau, November 6th – 7th





#### André Weidauer

**Fraunhofer Institute for Organic Electronics, Electron Beam and** Plasma Technology FEP

Dresden, Germany









# Content

**Fraunhofer FEP** 

Development of the toroidal source

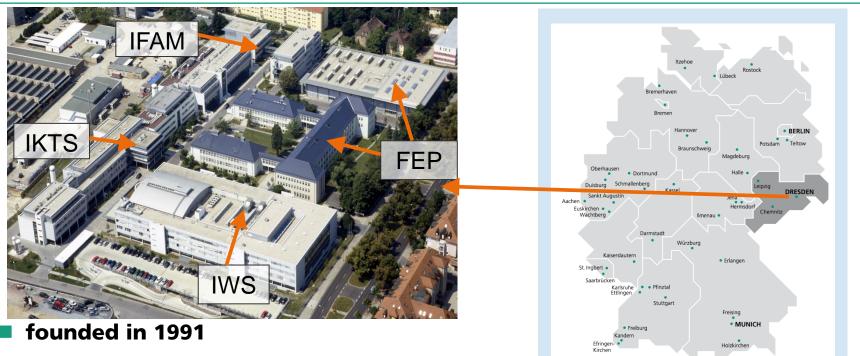
Application







## Fraunhofer FEP Fraunhofer Institute Center Dresden



#### premises: approx. 8,000 m<sup>2</sup>

- IFAM: Fraunhofer Institute for Manufacturing Technology and Advanced Materials
- IKTS: Fraunhofer Institute for Ceramic Technologies and Systems
- IWS: Fraunhofer Institute for Material and Beam Technology

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# **Fraunhofer FEP** Technical Equipment

#### **Laboratory System**

**Pilot System** 

Upscaling of processes





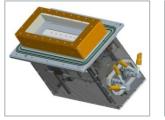


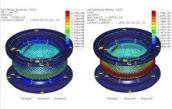


### Fraunhofer FEP Development of key components

- Division Systems
  - Group Mechanical Development
  - Group Electronic Development
  - Manufacturing

Mechanical Development: 3-D-Design / Strenght anaylses FEP





Design, Installation und put into use of regulation units and power supplies





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© Fraunhofer FEP Dipl.-Ing. André Weidauer Manufacturing: production of turned and milled parts



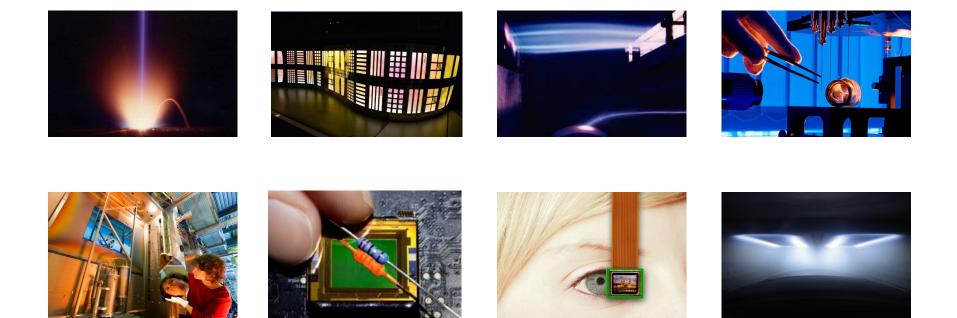
Software Development for all visualizations of processes:

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15	D D D			1	OutProgram	
Calls PCU-Send Set Press 20101	ARC valve	00	00	00 %	Cear Message	



### Fraunhofer Institute for Organic Electronics, Electron Beam and Plasma Technology FEP

#### Evolution of Surface.









Fraunhofer FEP

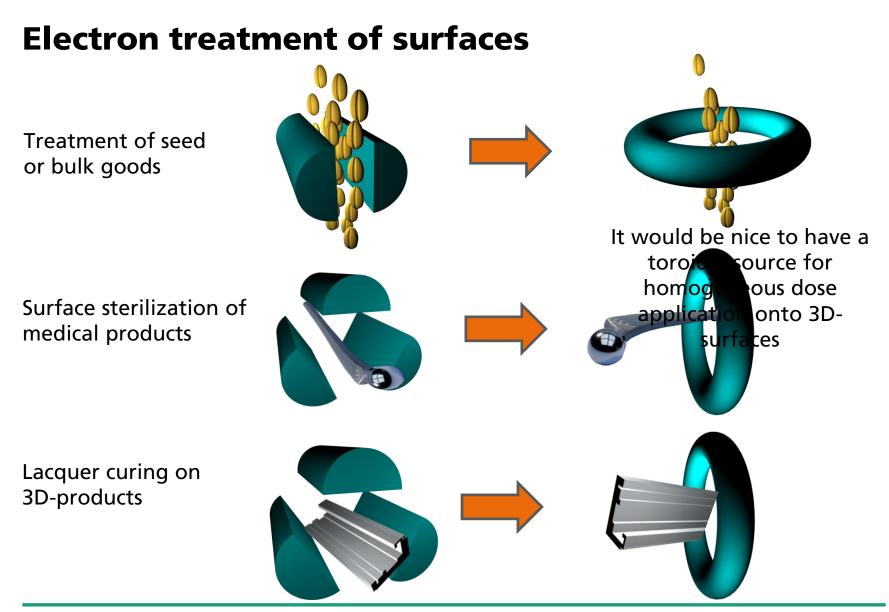
#### **Development of the toroidal source**

Application













## **Development of the toroidal source** Development steps

Concept phase 2008 - 2011

Development phase 2011 – 2013

Application development 2013 – 2017







# **Development of the toroidal source** Concept phase – Plasma EB

#### WHY COLD CATHODE?

- Free formable
- Fine-vacuum level required only
- Simple, cheap and longlife cathode principle without sensitive thin and hot wires
- Initial glow discharge plasma follows naturally the cathode shape -> different electron source shaping possible
- Easy controllable beam current by plasma density
- Decoupling of electron generation process and acceleration







# **Development of the toroidal source Concept phase – Plasma EB**

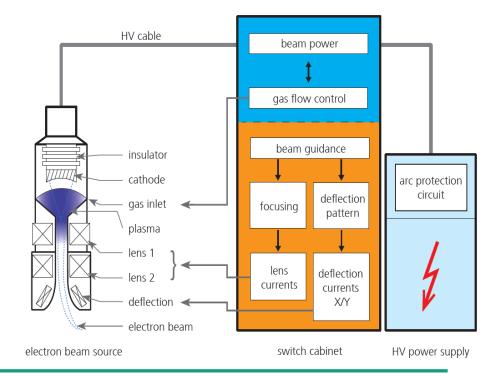
- Cold Plasma EB Sources
- Approved for high power axial guns

#### SPECIFICATION

Acceleration Voltage: **Beam Current: Rated Power:** Focus diameter: Deflection angle: Scanning frequency: Cathode material: Plasma work gases: Cathode service life: Operation pressure:



0 ... 15 A  $< 600 \, \text{kW}$ < 20 mm  $\pm 45^{\circ}$  $< 1 \, \text{kHz}$ Aluminum H2, He, ... > 120 h < 2.0 Pa

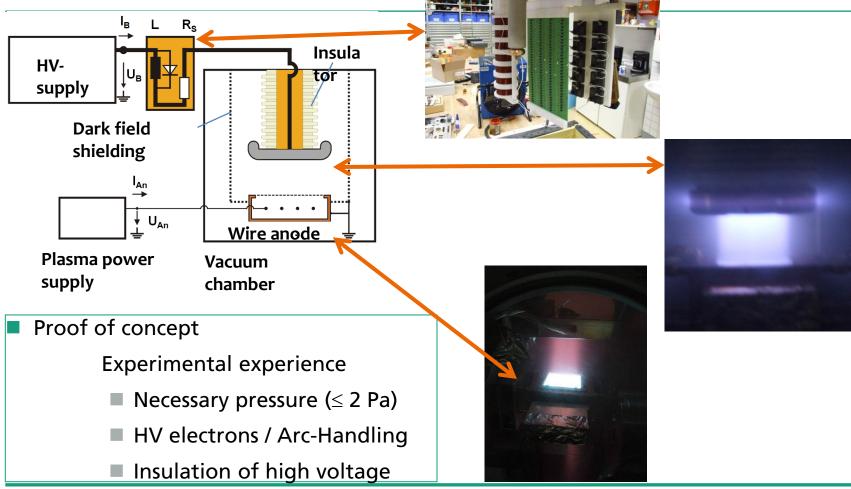






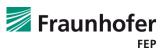
# **Development of the toroidal source**

**Concept phase – first tests** 



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# Development of the toroidal source

### **Development phase - Concept**

# projected application area, state of development

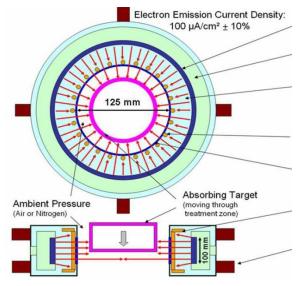
#### EB-Source for non-thermal processing

- Sterilization
- Seed treatment
- Polymer modification

#### New development

- Cold cathode electron source, which is stimulated by low pressure DC plasma
- Acceleration voltage > 100 kV
- Radial converging beam in order to have an all side product treatment in single pass







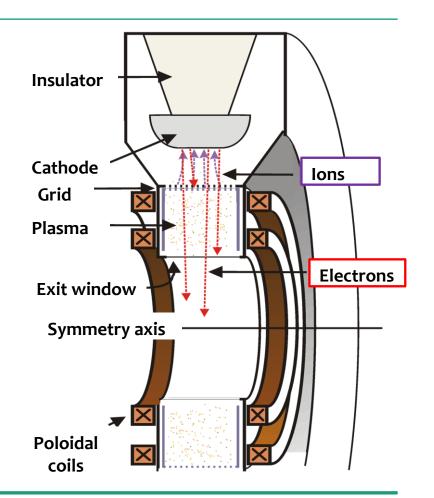


# **Development of the toroidal source** Development phase - Geometry

- New geometry (ring shaped convergent beam)
- Wire anode based on auxiliary discharge is replaced by magnetically driven ExB discharge
  - $\rightarrow$  Simple design!
- However: It is required an accurate knowledge of the coils and their effects
  - No previous experimental study was possible
  - Does the axial magnetic field disturbs the radial beam propagation?
- Numerical simulation of electron beam traces are the basis of dimensioning

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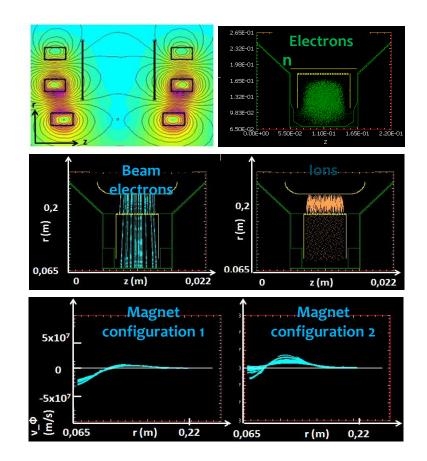




# **Development of the toroidal source** Development phase – Simulation

#### **TOROIDAL SOURCE WITH E x B - discharge**

- The auxiliary discharge ignition can be enhanced by the magnetic field at ~1 Pa, < 2000 A\*N, < 1kV</p>
- Different magnet configurations were found allowing useful beam traces
- To satisfy the plasma and beam trace conditions 3 coil pairs are necessary



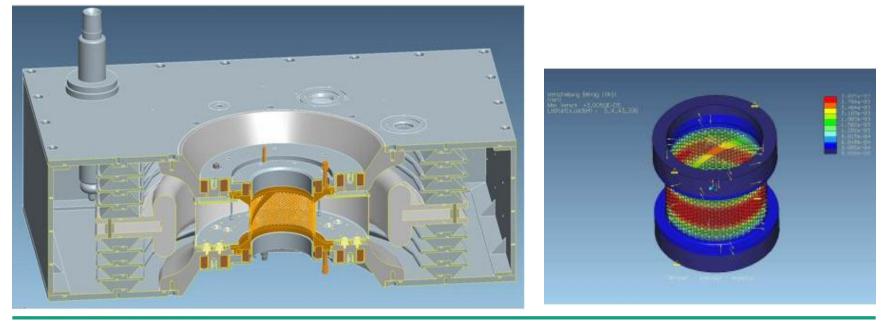




# **Development of the toroidal source Development phase – Design**

#### REQUIREMENTS

- Compact setting, reasonable price of basic raw materials
- Integrated protection and arc inhibition circuit
- Operating parameters:  $\emptyset$  120 mm, U<sub>B</sub>= 120 kV, P < 5 kW (j < 0,2 mA/cm<sup>2</sup>)

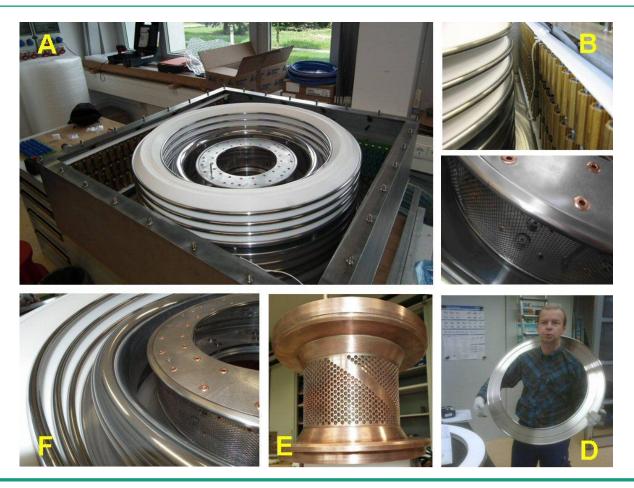








### **Development of the toroidal source** Development phase – Final assembly







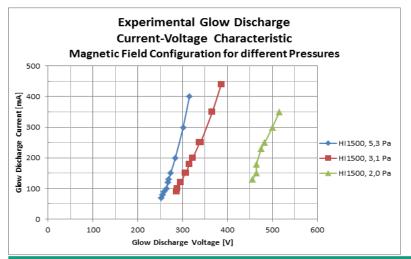


# Development of the toroidal source

### **Development phase – Characterization**

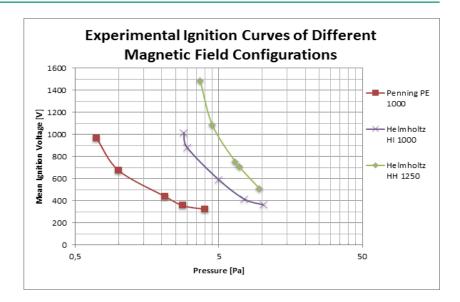
#### CHARACTERIZATION OF AUXILIARY DISCHARGE

- Investigation of ignition voltage behavior for possible working pressure
- Dependency of ignition voltage from the magnetic field configuration and power





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- The experimental results are predicted by the simulation with several magnetic field configurations
- Working pressure (1 5 Pa) can be lower than ignition pressure



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Development of the toroidal source

**Application** 







### Application **Applications of non-thermal electron beams**



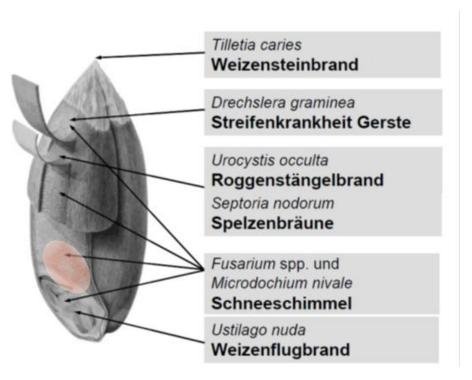






# Application **Electron treatment of seed**

- relevant pathogens onto or within the seed coat
- Pathogens inside the seed body and at the embryo can't be processed
- Cereal seed with ustilago affection will not accredited as seed
- *Fusarium* spp. can be treated partially only, but the practical experience is good, the economic significance under German conditions is low

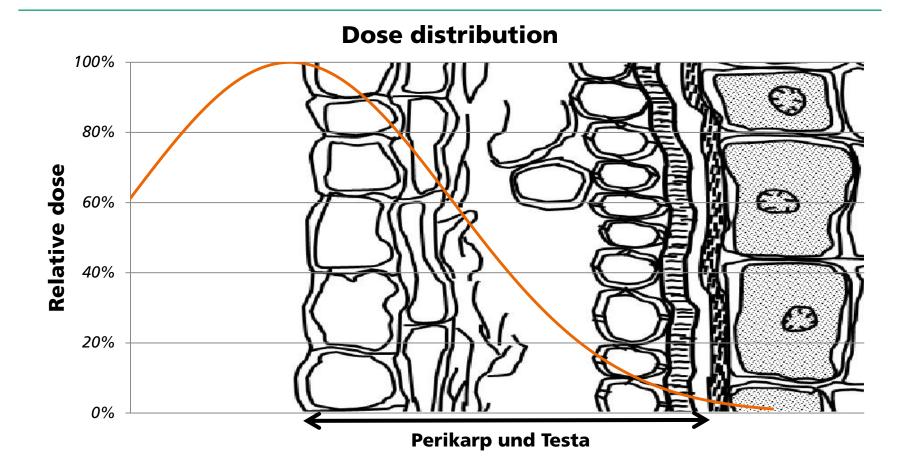








### **Application** Electron treatment of seed - Basic principle



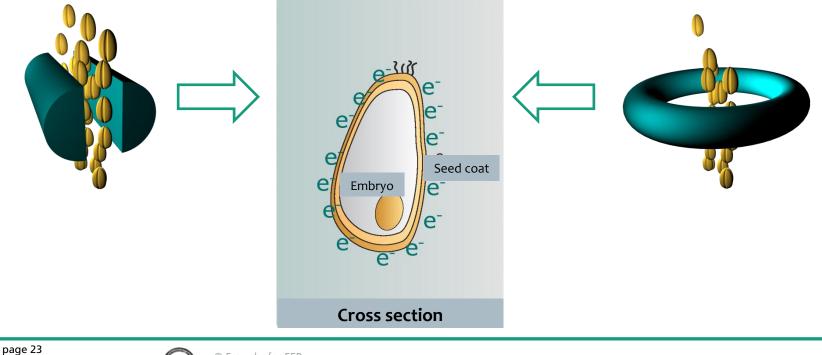






### **Application** Electron treatment of seed – state of the art

- Governmental funded project (Federal Ministry of Food, Agriculture and Consumer Protection)
- $\rightarrow$  compact, modular electron beam sources for seed treatment



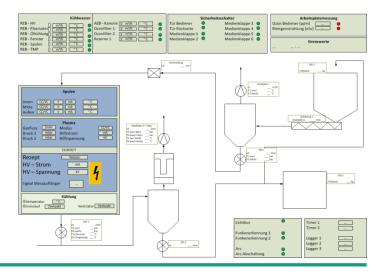




### **Application** Electron treatment of seed – new toroidal source

- Basic requirements for seed treating
  - U<sub>Bmax</sub> = 150 kV
  - I<sub>B</sub> = 10 mA
  - m/t = 5 t/h
  - Continuous process → stable plasma
- Additional requirements
  - Visualization
  - Window protection and cooling
  - Seed supply system









# **Application** Future projects

- Treatment of new products
  - Nuts
  - Fruits (Banana, Apples)

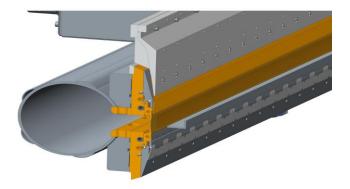
- Treatment of 3D- shaped products
  - Medical products
  - Polymer shapes
  - Lacquered products

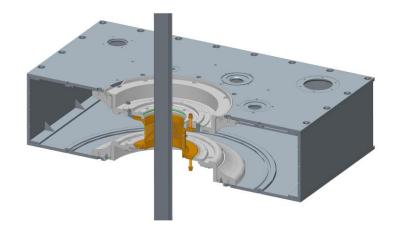


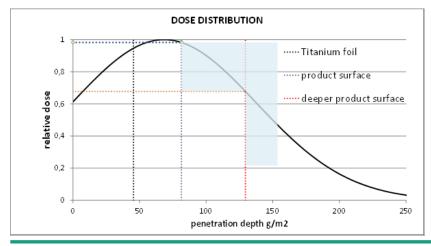


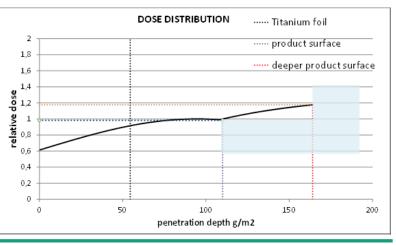


# **Application Future projects – L-shaped product**









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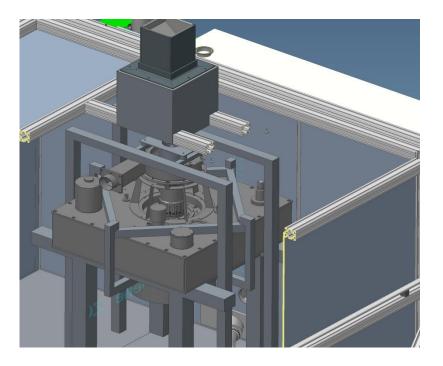




### **Application** Electron treatment of seed – status

#### ACKNOWLEDGMENT

- Dr. Gösta Mattausch at all
  - Dr. P. Feinäugle
  - F. Winckler
  - S. Schmidt
- Fraunhofer Gesellschaft
  - Funding the basic research
- Federal Ministry of Food, Agriculture and Consumer Protection
  - Funding the actually application development









### Thank you for your attention



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